

SUBSTRATE PROCESSING SYSTEM AND MAINTENANCE METHOD**Abstract**

5 A substrate processing system comprising a substrate
processing device, a vacuum transport chamber, a transport
mechanism, a suction mechanism, and a control unit. The
substrate processing device includes a vacuum processing
chamber in which vacuum processing is performed on a substrate.
10 The vacuum transport chamber is connected to the vacuum
processing chamber, and includes a transport opening that can
be communicated with the vacuum processing chamber. The
transport mechanism is disposed in the vacuum transport
chamber to transport the substrate through the transport
15 opening. The suction mechanism is disposed in the vacuum
transport chamber adjacent to the transport mechanism, to
suction a deposit on a component in the vacuum processing
chamber through the transport opening. The control unit
controls the transport mechanism and the suction mechanism.

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Fig. 3